

Title (en)

Electroplating process

Title (de)

Verfahren zum galvanischen Aufbringen einer Oberflächenbeschichtung

Title (fr)

Procédé d'électrodéposition

Publication

EP 0565070 B1 19970730 (DE)

Application

EP 93105726 A 19930407

Priority

DE 4211881 A 19920409

Abstract (en)

[origin: US5415761A] A process for electrochemically depositing a structured surface layer on a component, such as a machine component, particularly a steel water cylinder of a printing press, is disclosed. The process comprises the steps of defining an electrical parameter, such as a potential and/or an electrical current, effecting an electro-chemical layer deposition; and depositing a surface layer on the component with a structured outer surface topography. The depositing step is performed by providing an initial pulse of the electrical parameter and forming a plurality of island formations of deposition material on a surface of the component to be electro-chemically coated, and subsequently providing a follow-up pulse of the electrical parameter and causing a growth of the deposition material on the plurality of islands for causing the structured outer surface topography.

IPC 1-7

C25D 5/18

IPC 8 full level

C25D 5/16 (2006.01); **C25D 5/18** (2006.01)

CPC (source: EP US)

C25D 5/14 (2013.01 - EP US); **C25D 5/18** (2013.01 - EP US); **C25D 5/605** (2020.08 - EP US); **C25D 5/625** (2020.08 - EP US)

Cited by

EP4012074A1; EP3000918A1; CN111201340A; US11136685B2; US11732373B2; EP3438330A1; WO2019025203A1

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